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		2,302,024	11/17/1942	Goss, Jr						
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V		4,883,563 11/28/1989 Kot			et al.			i		
BT		6,056,526	05/02/00	Sato						
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	3,743,842	07/03/1973	Smith,	H.I., et al.				
	4,310,743	01/12/1982	Seliger,	R.L.				
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y	4,606,788	08/19/1986	Moran,	P.L.				
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151	98/26913	06/25/1998	PCT		†		-	
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		4,325,779	04/20/1982	Rossett	i, J.J.				
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		5,277,749	01/11/1994	Griffith	h, J.H., et al.				
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	Nomura, et al., "Moire	Alignment Techn	ique for th	ne Mix and Match Litho 1988)	graphic System:	J. Vacuum So	ciety Techi	nol. B6
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